

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Tetsuo TANIGUCHI et al.

Group Art Unit: 2877

Application No.: 09/593,800

Examiner: P. Natividad

Filed: June 15, 2000

Docket No.: 106514

For: STAGE DEVICE AND EXPOSURE APPARATUS

AMENDMENT FILED WITH RCE

Director of the U.S. Patent and Trademark Office  
Washington, D.C. 20231

Sir:

Further to the December 16, 2002 Notice of Allowance, and after entry of the Request for Continued Examination (RCE) filed herewith, please amend the above-identified application as follows:

IN THE CLAIMS:

Please add the following claims 32-42:

E1 --32. (New) The stage device according to claim 2, wherein the first measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.--

--33. (New) The stage device according to claim 32, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.--

--34. (New) The stage device according to claim 2, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.--

--35. (New) A scanning exposure apparatus, comprising:  
a reticle stage which is movable and holds a mask having a pattern;

